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Lattice-matched III-V solar cells: progress and application opportunities

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www.research.tuni.fi/orc

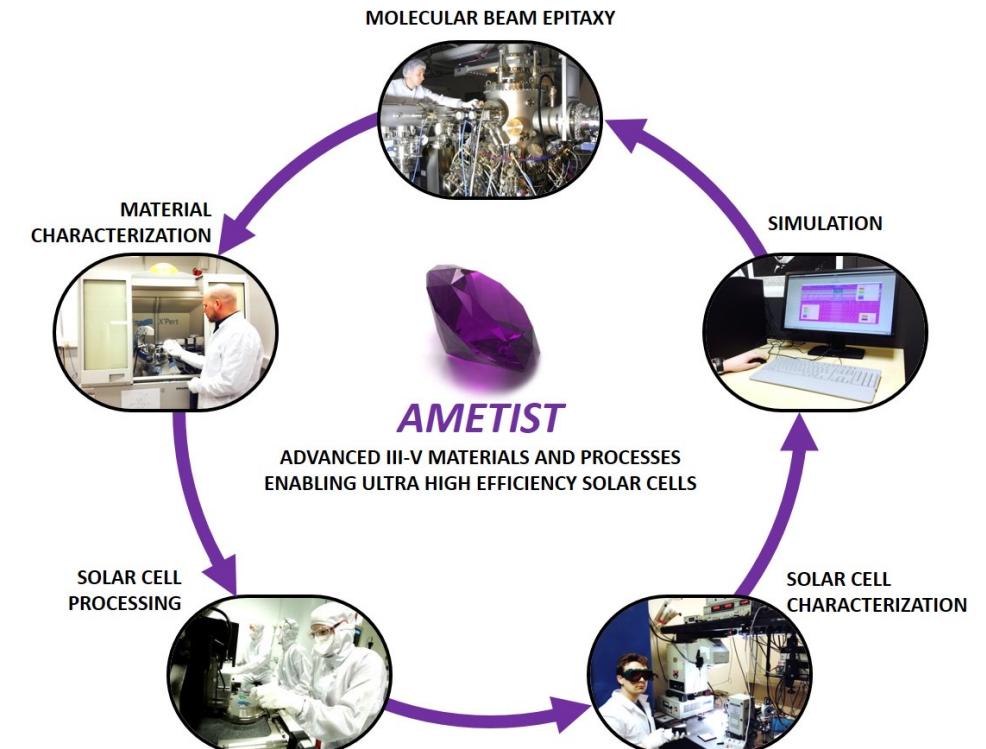
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Outline

- Motivation
- Epitaxy of lattice-matched GaInNAsSb heterostructures on GaAs
 - State-of-the-art 0.7-0.8 eV junctions
- Progress in developing 4J/5J/6J lattice-matched solar cells
- Forward looking conclusions



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<https://projects.tuni.fi/amatist/>

Motivation

Multijunction III–V solar cells

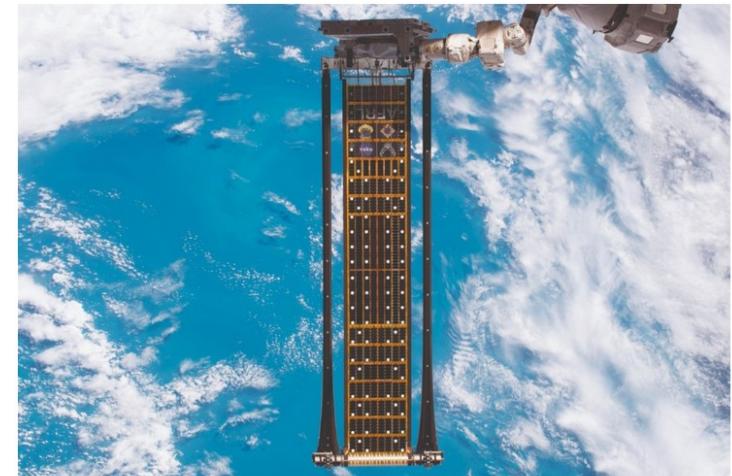
- Key technology for space solar power
- Terrestrial applications in CPV systems

The quest for higher efficiencies

- Reduced weight/power ratio for satellites
- Increased economic feasibility for CPV

Standard monolithic technology limited to 4J architectures (MOCVD based; requires thick metamorphic buffers)

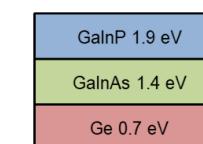
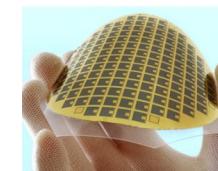
Advanced functionality: thin-film flexible solar cells (proven for lattice-matched architectures)



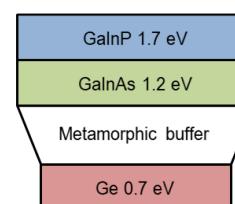
Flexible solar cells are needed on the ROSA (Roll Out Solar Array) held by the robotic arms at the International Space Station.

CS Mag. Oct. 2021

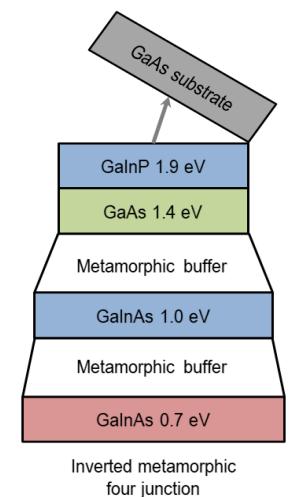
tf2devices.com



Lattice-matched triple junction



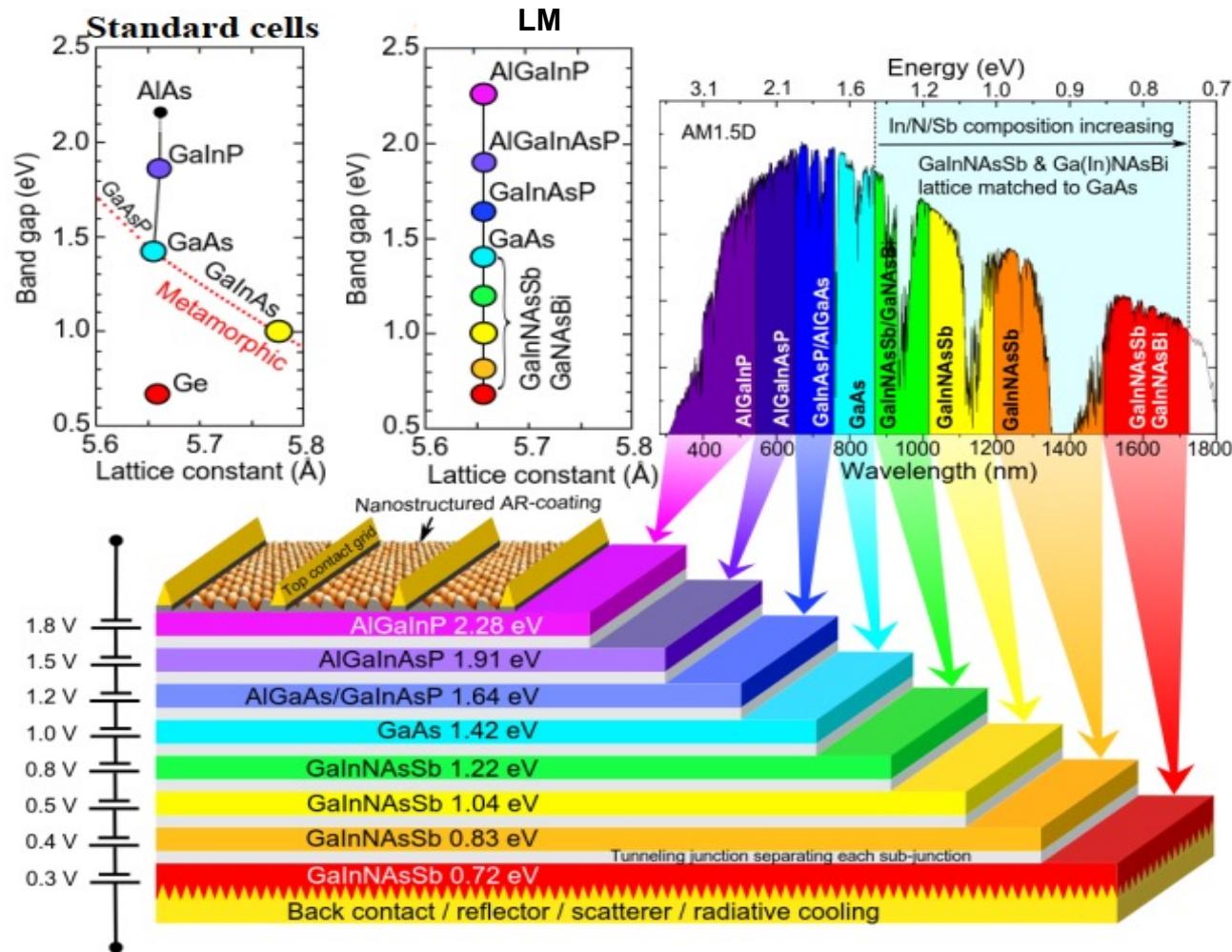
Upright metamorphic triple junction



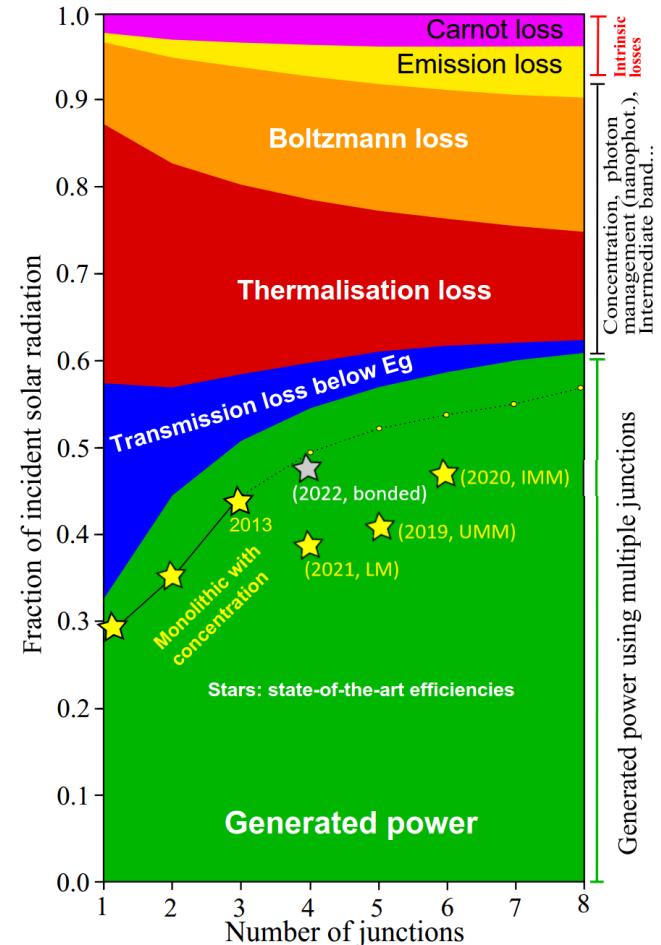
Inverted metamorphic four junction

R. France et al., MRS Bulletin, Mar. 2016

Lattice-matched dilute nitride architecture

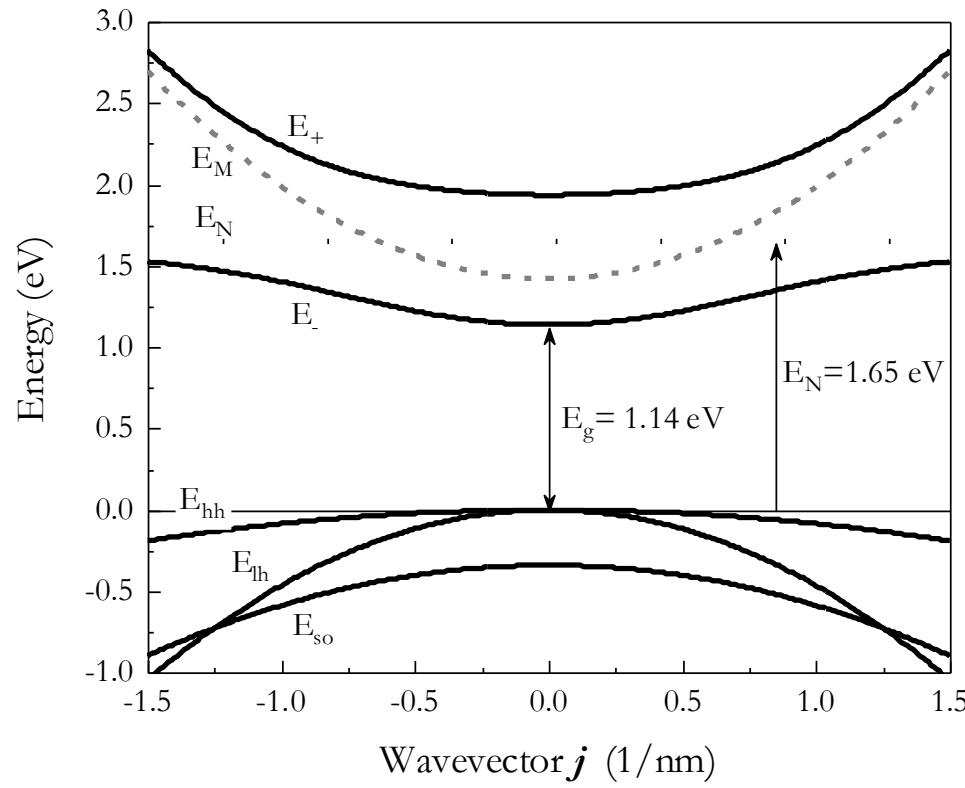
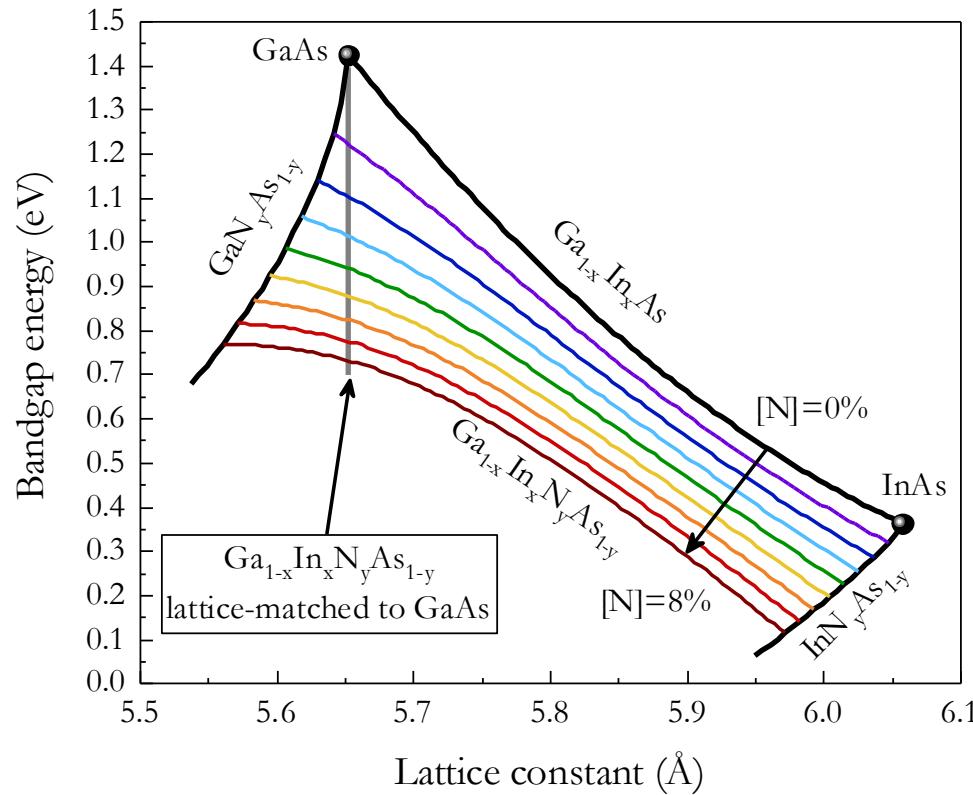


Key issues: material quality and current-matching



Adapted from Hirst, Ekins-Daukes:
Fundamental losses in solar cells," *Prog. in
PV: Res. and App.*, 2011

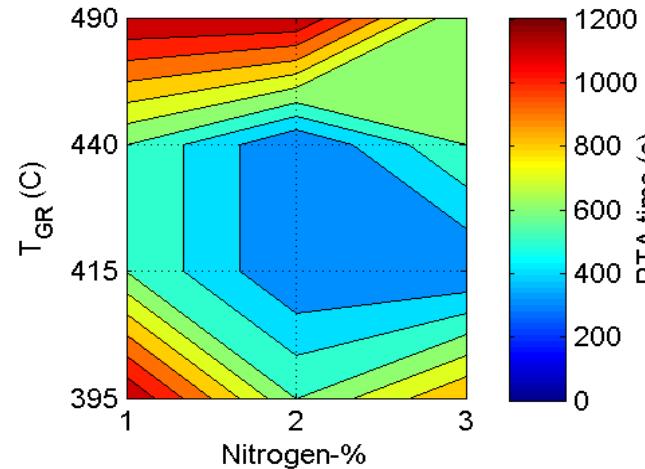
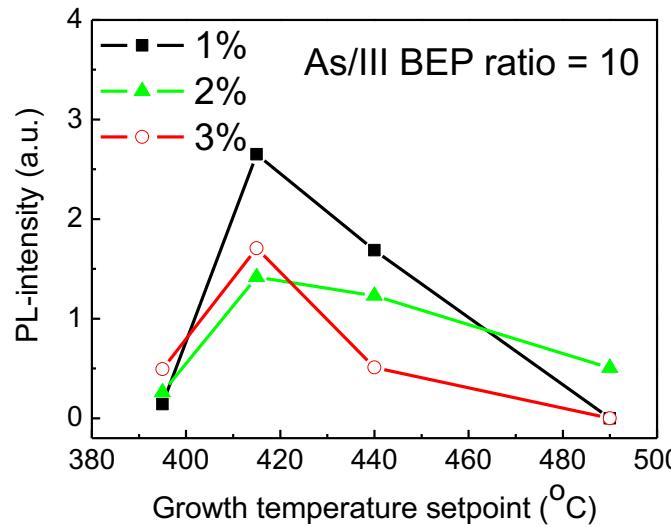
Bandgap engineering with dilute nitrides



Electronic band structure for $\text{GaN}_{0.02}\text{As}_{0.98}$ (BAC)

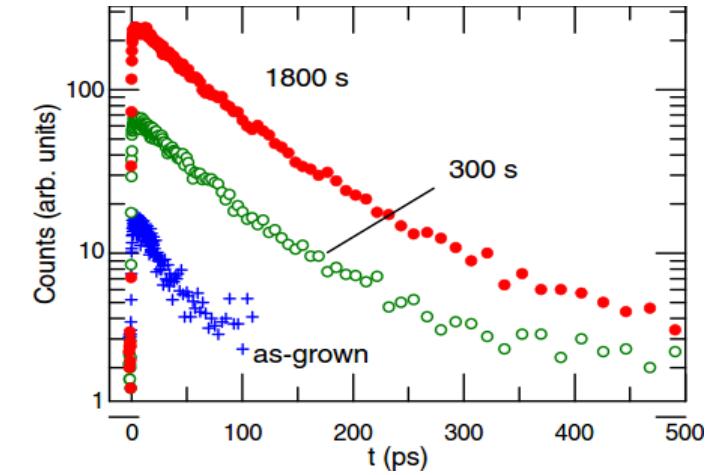
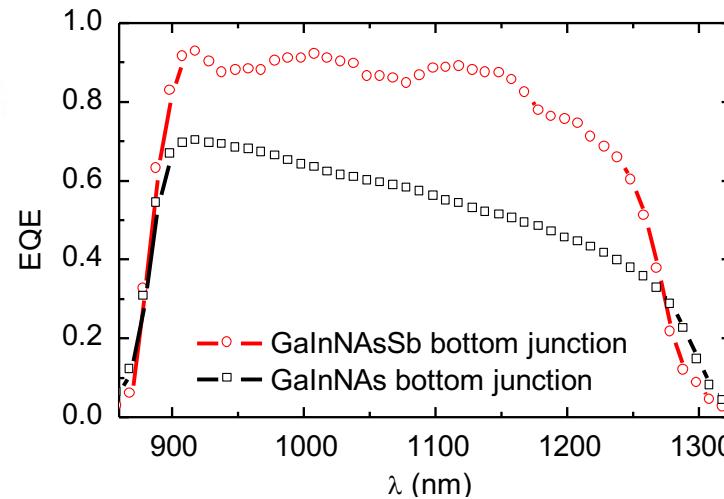
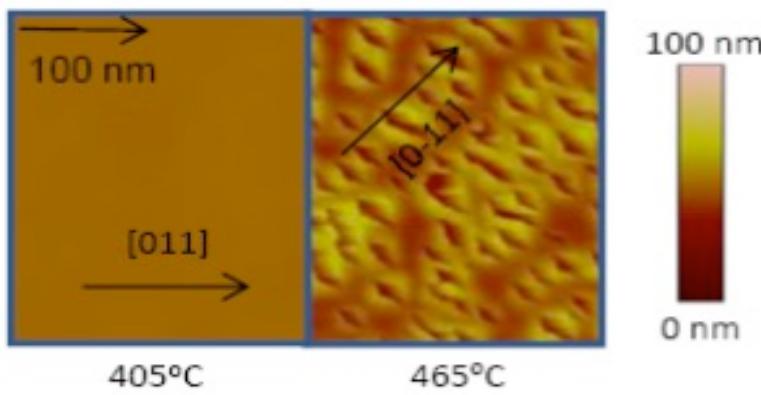
Reaching 0.7-0.8 eV on GaAs requires 6-8% of nitrogen

MBE growth of 1 eV GaInNAsSb junctions

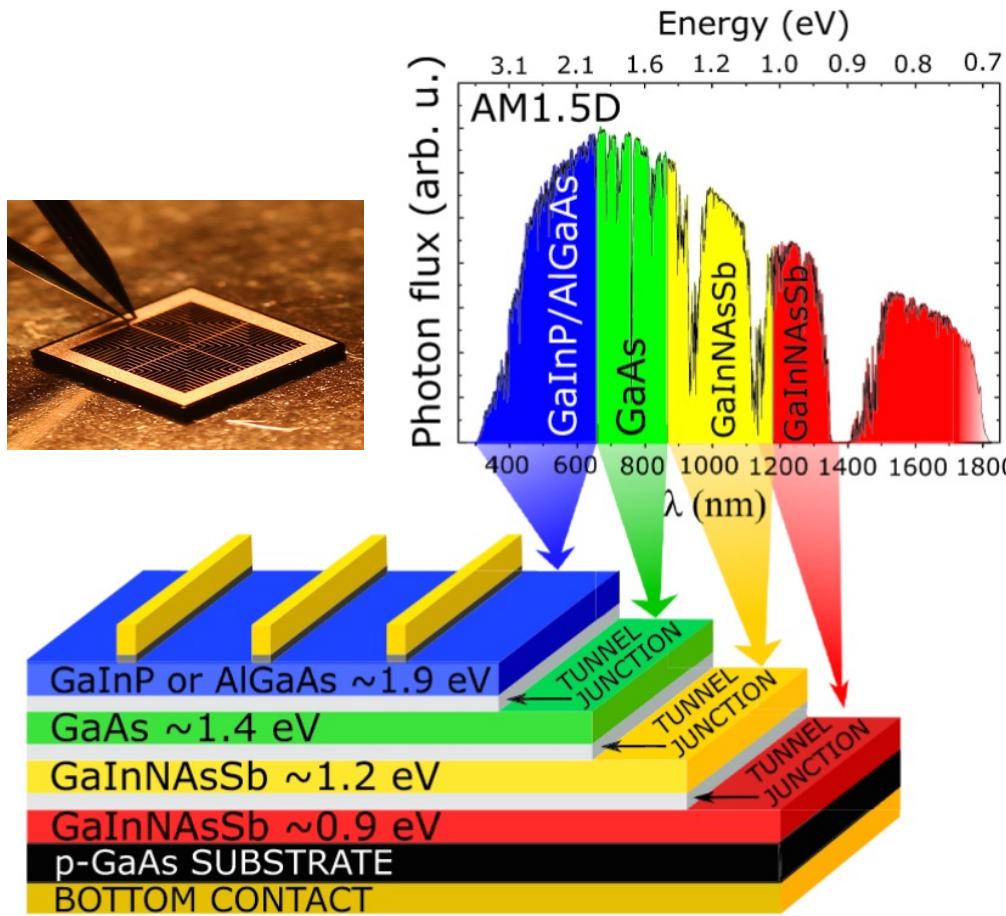


Parameter	Value
Doping type	p
Doping level	$< 1 \times 10^{16} \text{ cm}^{-3}$
Electron mobility	$350\text{-}400 \text{ cm}^2/\text{Vs}$
Hole Mobility	$80\text{-}100 \text{ cm}^2/\text{Vs}$
Carrier lifetime	$> 0.5 \text{ ns}$

Requirements for GaInNAsSb junctions

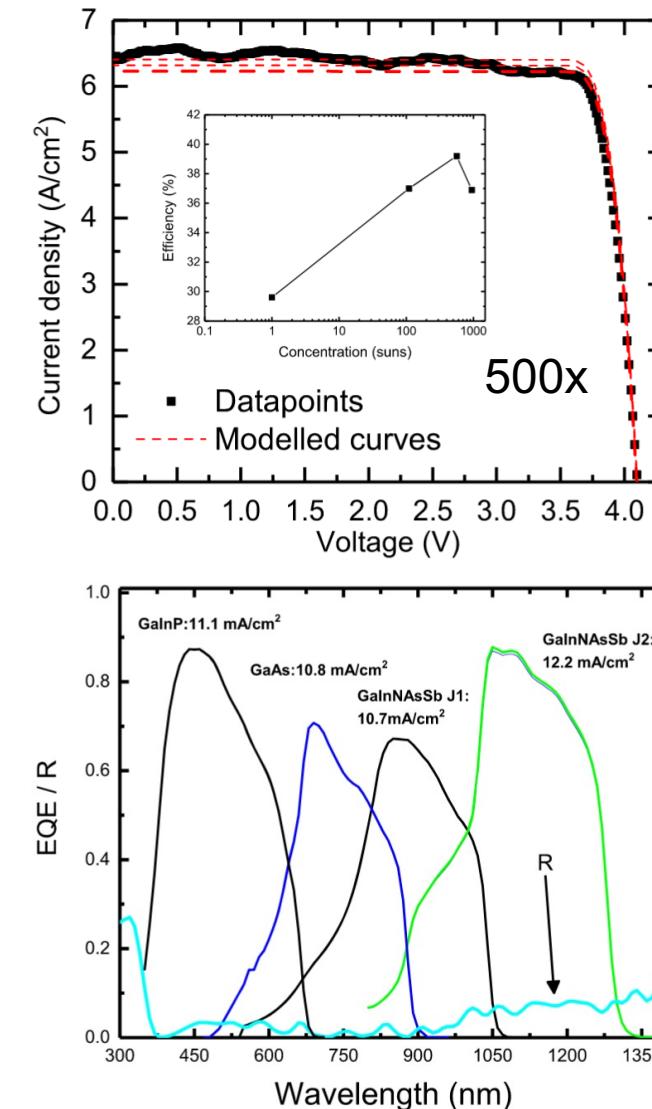


4J cells with two GaInNAsSb junctions



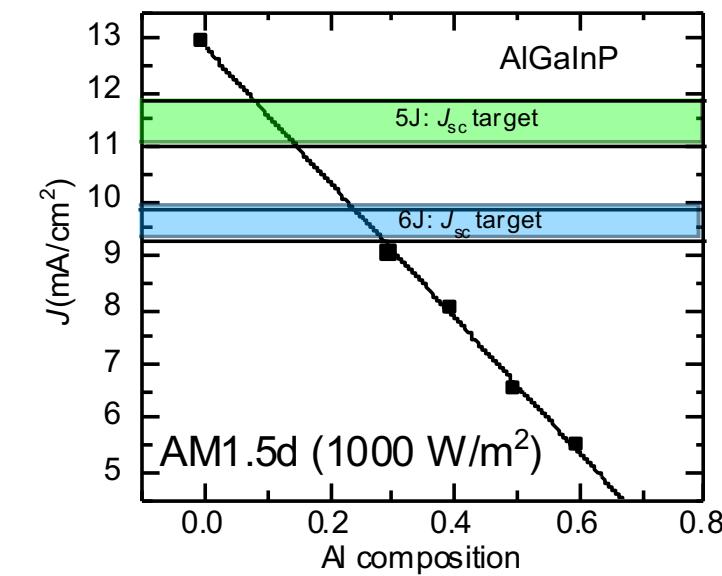
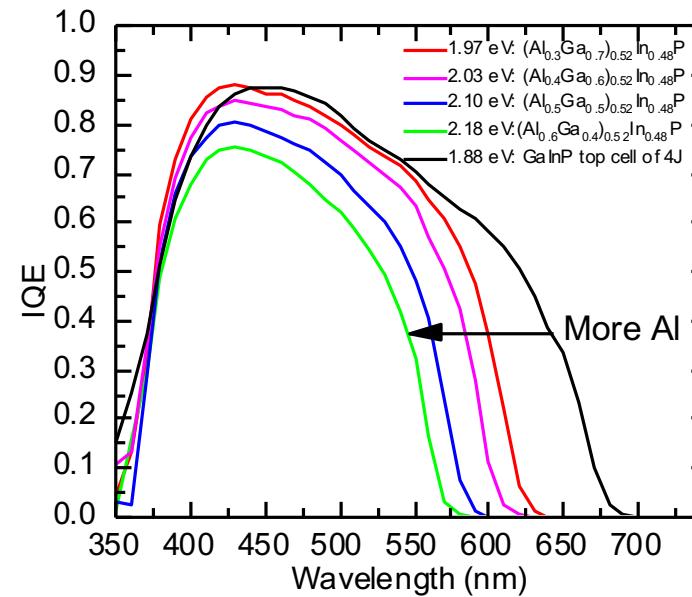
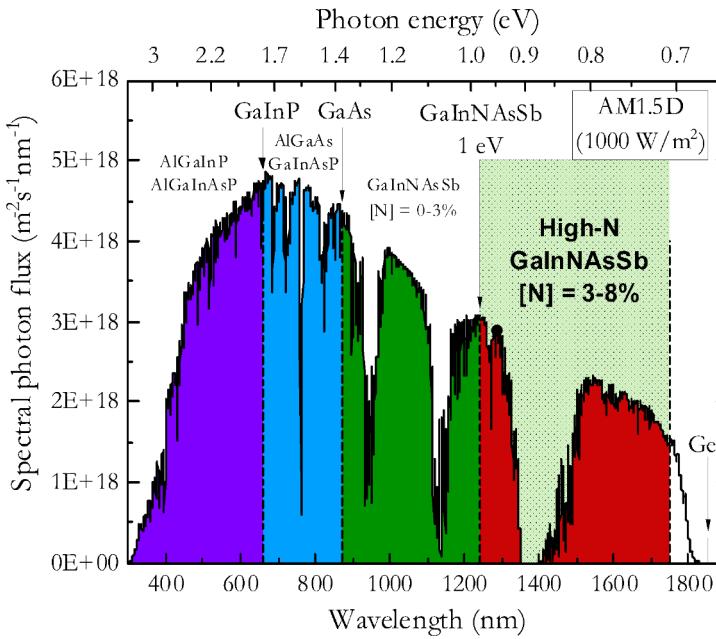
4J with two dilute nitride bottom junctions

Aho et al., Prog Photovolt Res Appl. 29: 869– 875 (2021)



Lattice-matched designs with 5+ junctions

- Extension to long wavelength using GaInNAsSb junctions with $E_g < 0.9$ eV ($[N] > 5\%$)
- Current matching also requires development of AlGaInP top junction (> 2 eV)



Epitaxy optimization of 0.8 eV GaInNAsSb

- Lattice-matched high-N p-i-n junctions grown on 4" p-GaAs
- E_g target~0.8 eV (N ~5-6%; In ~ 15%; Sb ~2-3%)
- Change of growth parameters: T_g , As/III BEP ratio, Sb flux
- All samples *in-situ* annealed

Sample	[In] _{nominal} (%)	[N] _{nominal} (%)	T_g (°C)	As/III BEP ratio	Sb BEP (Torr)
A	15	5.2	440	9.0	1.0×10^{-8}
B		5.7	440	9.0	1.0×10^{-8}
C		5.2	450	9.0	1.0×10^{-8}
D		5.2	460	9.0	1.0×10^{-8}
E		5.0	470	9.0	1.0×10^{-8}
F		5.0	480	9.0	1.0×10^{-8}
G	15	5.0	470	7.0	1.0×10^{-8}
H		4.9	470	5.2	1.0×10^{-8}
I	15	4.8	470	7.0	1.4×10^{-8}
J		4.8	470	7.0	1.8×10^{-8}
K		4.8	480	7.0	1.8×10^{-8}

T_g

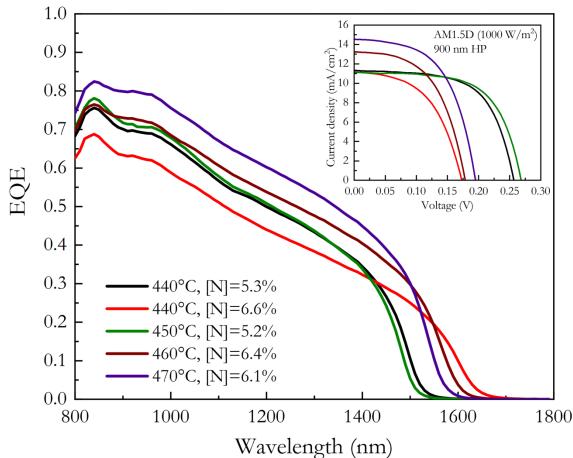
As

Sb

n-GaAs	300 nm	$1 \times 10^{19} \text{ cm}^{-3}$	Contact layer
n-Al _{0.35} Ga _{0.65} As	40 nm	$2 \times 10^{18} \text{ cm}^{-3}$	Window
n-GaAs	100 nm	$1 \times 10^{18} \text{ cm}^{-3}$	Emitter
i-GaInNAsSb	1.2 μm		Absorber
p-GaAs	100 nm	$5 \times 10^{18} \text{ cm}^{-3}$	Base
p-Al _{0.35} Ga _{0.65} As	100 nm	$5 \times 10^{18} \text{ cm}^{-3}$	BSF
p-GaAs	300 nm	$5 \times 10^{18} \text{ cm}^{-3}$	Buffer
p-GaAs substrate (625 μm)			

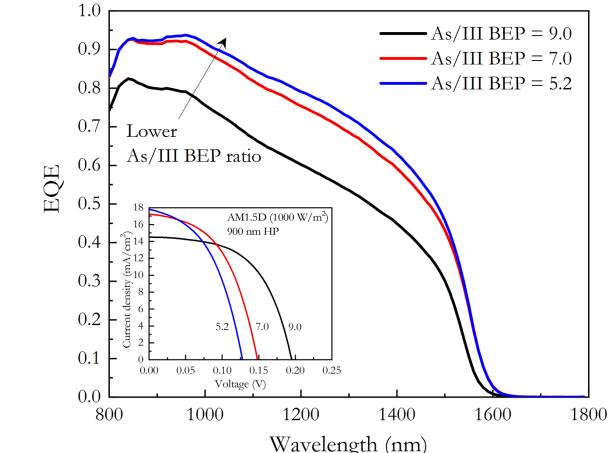
Isoaho *et al.*, Sol. Energy Mater. Sol. Cells (2022)

Effects of growth parameters



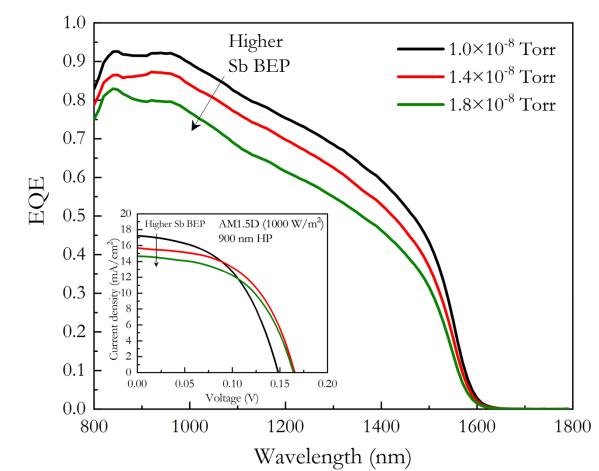
$T_g \uparrow$:

- Enhanced N incorporation at ≥ 460 °C
 - More recombination with higher N
 - Carrier lifetimes 4-5 ns → < 1 ns
 - Reduction of V_{oc}
- Phase separation at 480°C
 - Suppressed with more Sb
- p-type background doping ↓
 - $10^{17} \text{ cm}^{-3} \rightarrow 10^{16} \text{ cm}^{-3}$
 - EQE and J_{sc} ↑



$As \downarrow$:

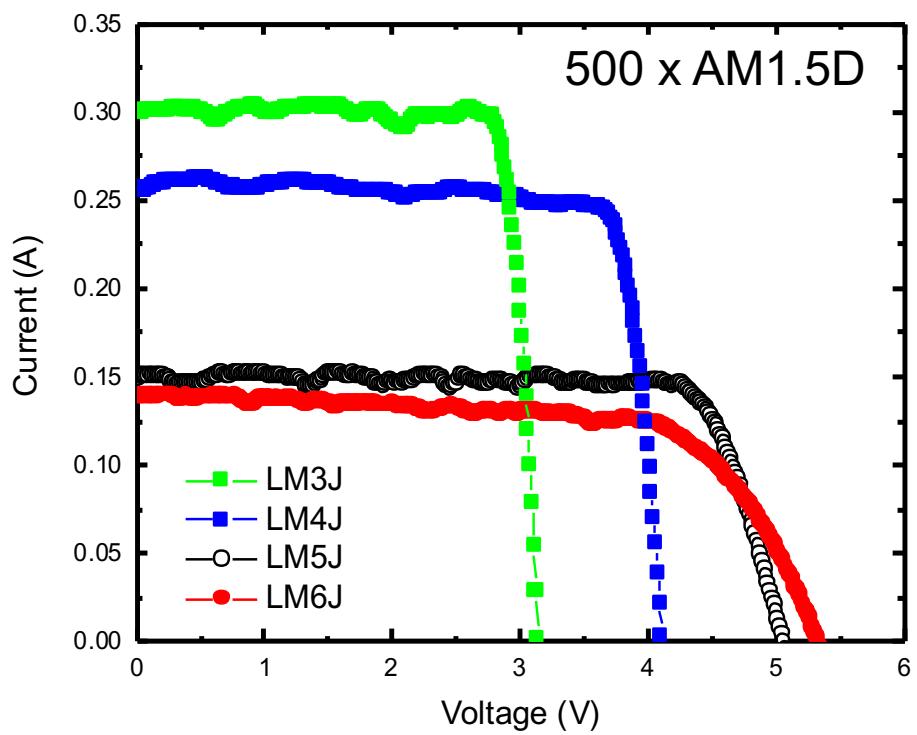
- Enhanced N and Sb incorporation
 - More recombination with higher N
 - Carrier lifetimes 1.5 ns → 0.5 ns
 - Reduction for V_{oc}
- p-type background doping ↓
 - $2 \cdot 10^{16} \text{ cm}^{-3} \rightarrow 2 \cdot 10^{15} \text{ cm}^{-3}$
 - EQE and J_{sc} ↑
 - >90% EQE values achieved



$Sb \uparrow$:

- Slight reduction in recombination
 - Carrier lifetimes 0.6 ns → 0.7 ns
 - +20 mV for V_{oc}
- p-type background doping ↑
 - $2 \cdot 10^{15} \text{ cm}^{-3} \rightarrow 7 \cdot 10^{15} \text{ cm}^{-3}$
 - EQE and J_{sc} ↓
- Combined effect → +10% in output power with intermediate Sb

LM MJSCs: From 3 to 6 junctions

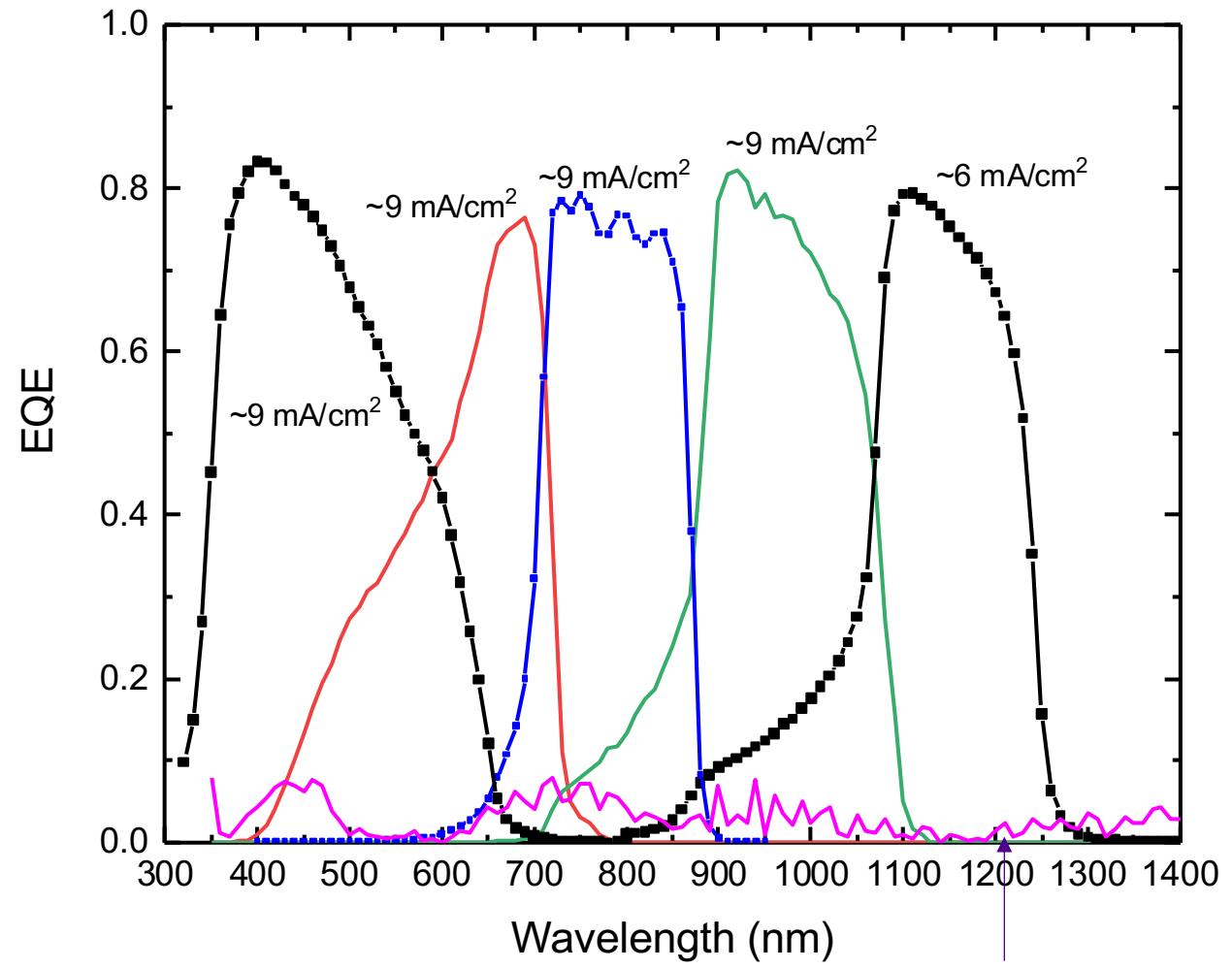


Measured LIV characteristics for lattice-matched solar cells under 500 x AM1.5D illumination.

LMSC	$J_{sc\text{-meas}}/J_{sc\text{-target}}$ (mA/cm ²)	V_{oc} (V)	Eg (eV)
3J	13/14	3.1	1.9/1.4/1.0
4J	11/12	4.1	1.9/1.4/1.2/0.9
5J	6/9	5.1	1.9/1.7/1.4/1.1/0.9
6J	6/8	5.3	1.9/1.7/1.4/1.2/1.1/0.8

5J:GaInP/AlGaAs/GaAs/GaInNAsSb/GaInNAsSb

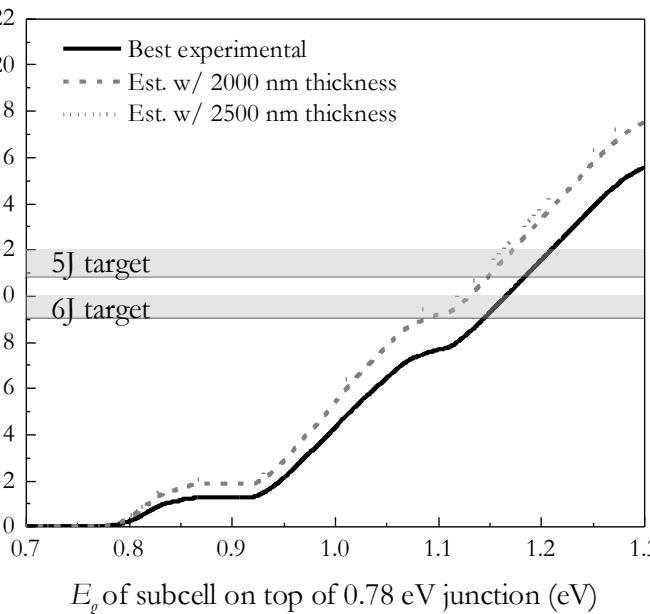
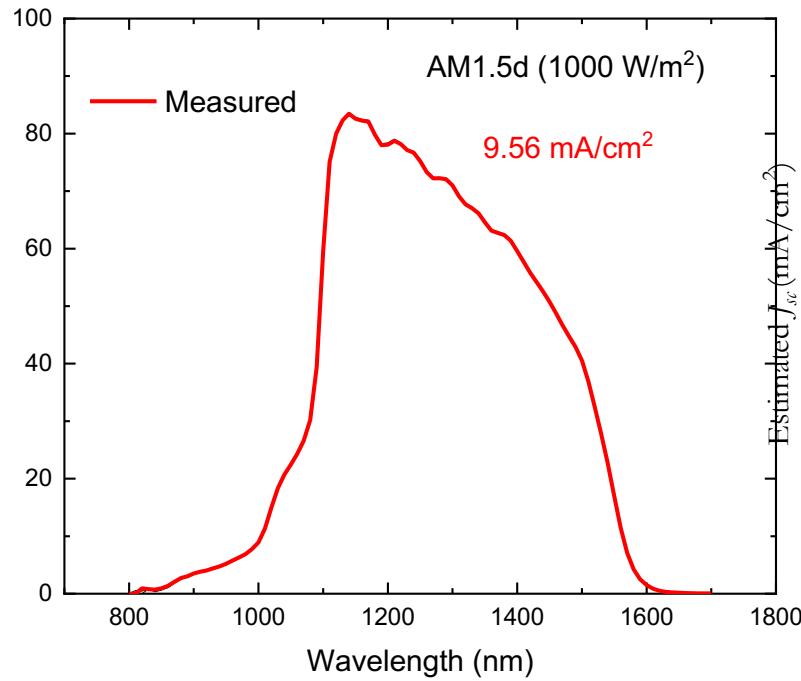
- 6 layers ARC coating
- Good voltage per junction
 $W_{oc} (500x) = 0.39 \text{ V}$ (similar to LM3J)
- Small cell area of 0.04 cm^2
- EQE: Bottom SC limits the J_{sc}
 - Too large E_g (6 mA/cm^2 vs. 9 mA/cm^2)



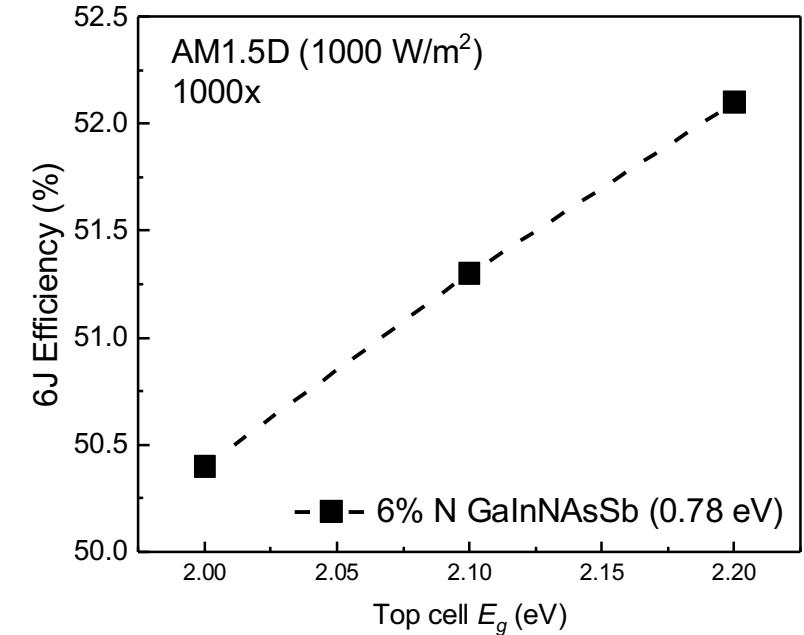
ARC

Prospects for 6J integration

- Current-matching for ~0.8 eV sub-cells is achievable
- Concentrated efficiencies exceeding 50% are realistic with 6J employing the best experimental 0.78 eV GaInNAsSb junctions (top junction require larger bandwidth)

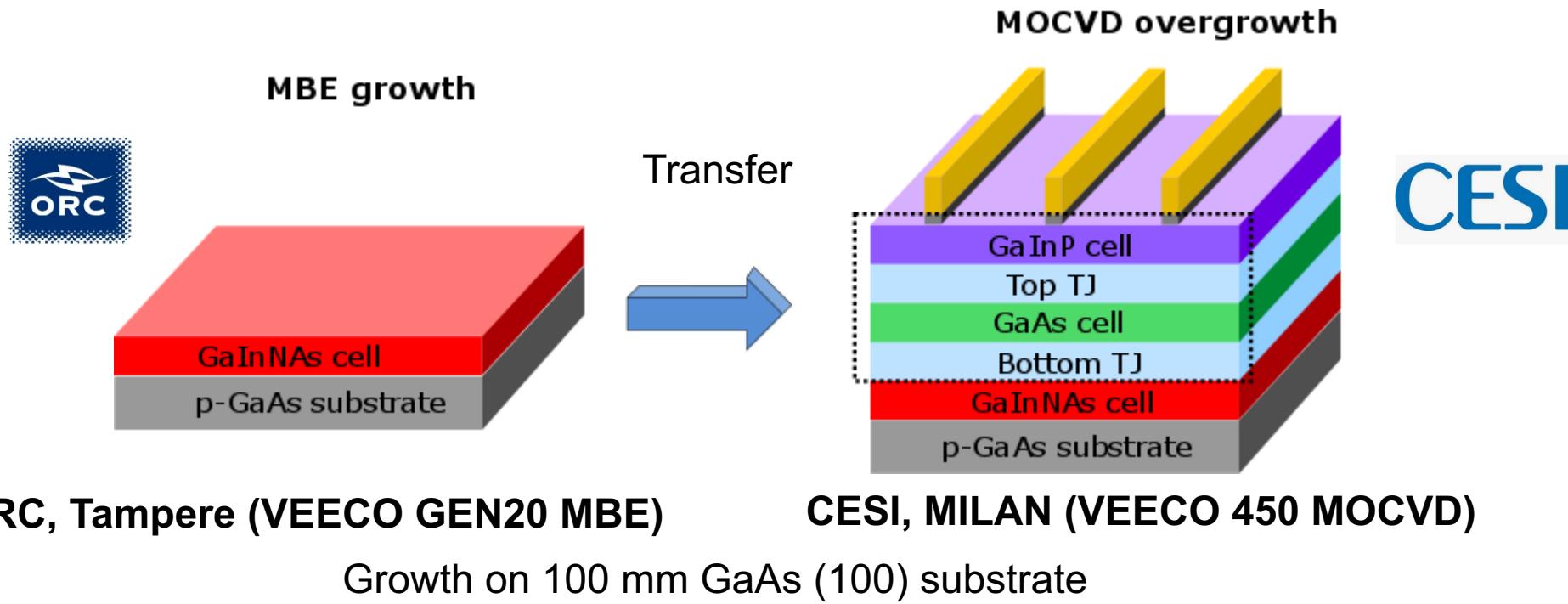


Isoaho et al., Sol. Energy Mater. Sol. Cells (2022)



Isoaho et al., Sol. Energy Mater. Sol. Cells (2019)

Technology compatible with MOCVD



Combines the technological and economic advantages of both the MBE and MOCVD processes to produce MJ solar cells at reduced cost and higher throughput with respect to MBE process.

Key issues: transfer process; nucleation layers; MOCVD thermal budget

A. Tukiainen et al., High-efficiency GaInP/GaAs/GaInNAs solar cells grown by combined MBE-MOCVD technique; 2016

MBE/MOCVD on Ge substrate



+

CESI

Public report ESA Project “Impro33”

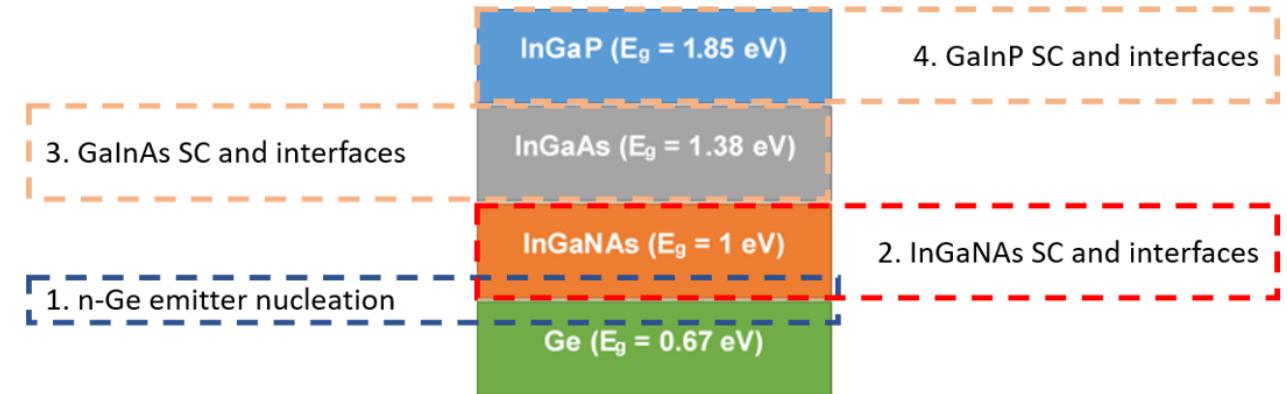
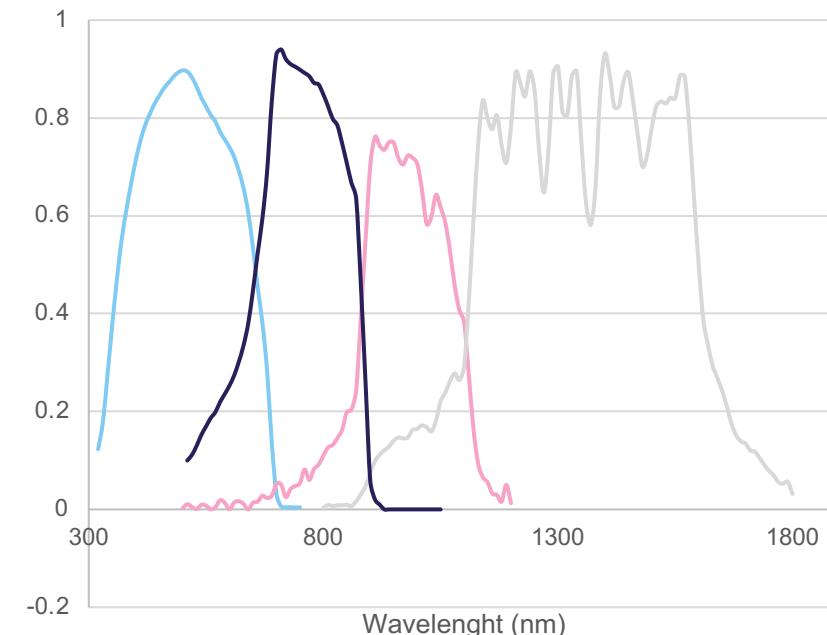
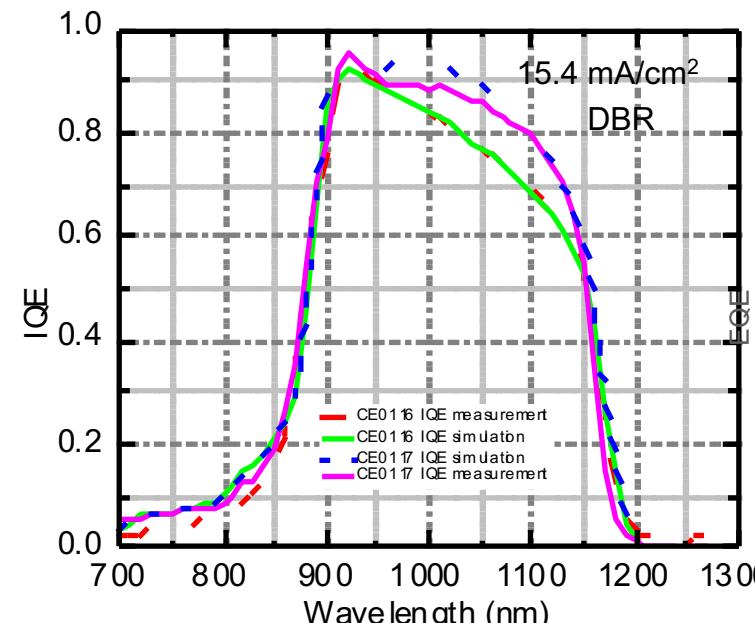


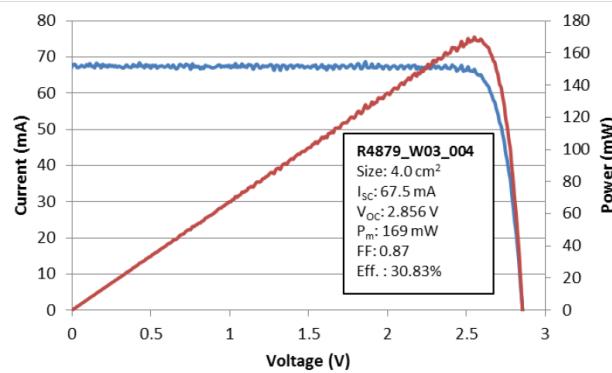
Fig. 2: Basic principle of the combined MBE-MOCVD technique.



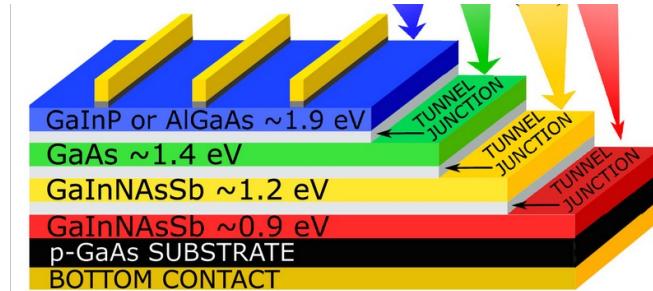
Forward looking conclusions

- MBE technology for dilute-nitride solar cells is mature enough for architectures with more than 4 junctions. Suitable for mass production.
- High quality low-bandgap GaInNAsSb materials ($N \sim 6\%$) demonstrated.
- The highest bandgap junction needs to be developed as well as several processing aspects (e.g., grid design, passivation, ARC, mounting etc.)
- The 50% efficiency target under CPV conditions is feasible.
- Lattice-matched solar cell technology is particularly attractive for implementing thin-film architectures for specialized applications.

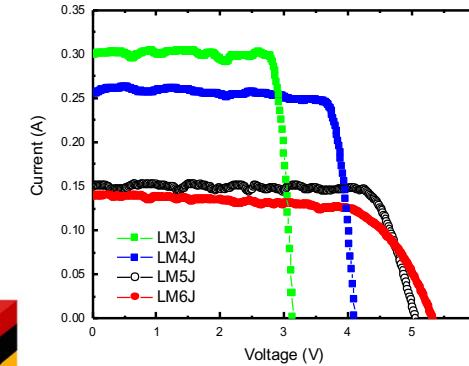
From materials to applications



2016: ~31% MBE-MOCVD Space 3J



2020: MBE CPV LM4J@ 500X



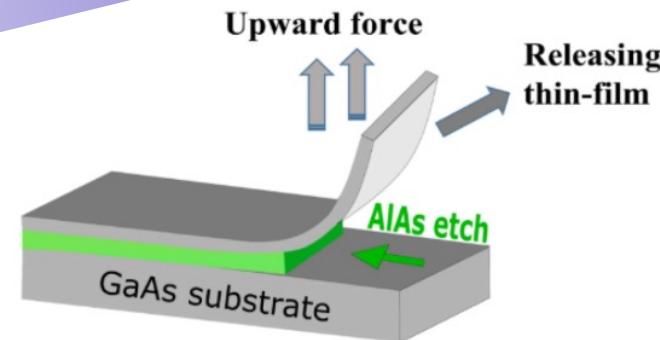
2022 ~0.8 eV GaInNAsSb
and 5-6 J prototypes



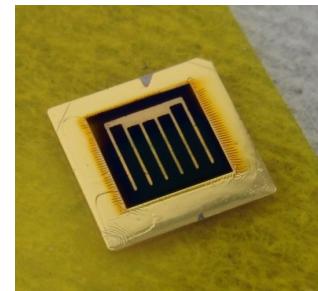
2023: Light-based
ENERGY solutions
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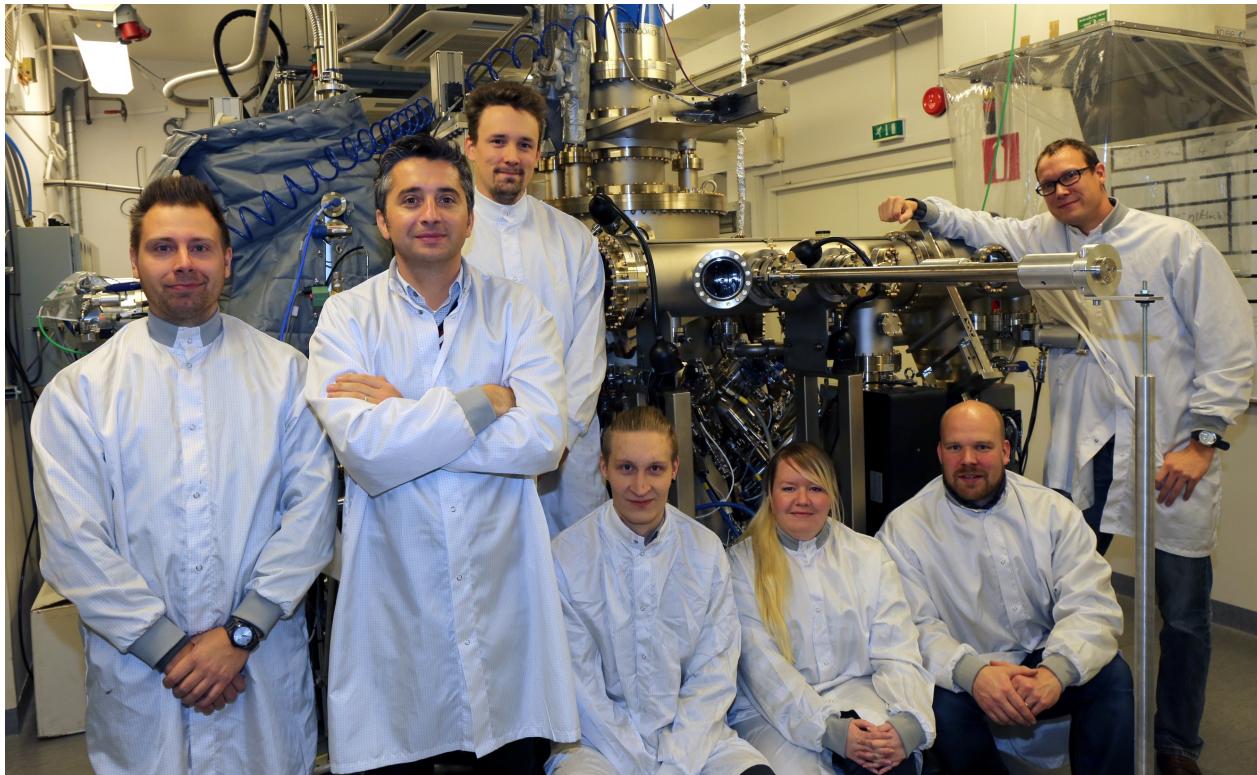


Prabudeva et al., “*Epitaxial lift-off process for GaAs solar cells controlled by InGaAs internal sacrificial stressor layers and a PMMA surface stressor*”, SolMat 248 (2022)



Thank you!

Dr. Antti Tukiainen, Dr. Arto Aho, Dr. Ville Polojärvi
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